

Divisional of S.N. 10/093,519 filed March 11, 2002

IN THE SPECIFICATION:

Amend the specification as follows:

After the title, please insert the following sentence:

This application is a divisional of application Serial No.: 10/093,519, filed March 11, 2002.

Please replace the paragraph beginning at page 23, line 7 with the following rewritten paragraph:

Referring to FIG. 10A, a BaO film 62 having a thickness of 5 to 6 ~~mm~~ nm is ~~deposited~~ deposited on a silicon substrate film 51 from which a natural oxide film has been removed through a HF process, by a pulse laser deposition technique using a BaCO₃ target as the target 15 shown in FIG. 2. In a procedure shown in FIG. 10B, a BaTiO₃ film 63 having a thickness of 200 ~~mm~~ nm is deposited on the BaO film 62 by a pulse laser deposition technique using a BaTiO₃ target as the target 15. During the procedures shown in FIGS. 10A and 10B, the heaters 12A and 12B are driven so as to maintain the substrate 13, the target 15, and the plume 14 at 800 °C. In the procedure shown in FIG. 10A, the BaCO₃ target is subjected to laser ablation under a

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pressure of 5×10^{-6} Torr for 1 minute and then in an oxygen atmosphere of 1×10^{-2} Torr for 2 minutes. In the procedure shown in FIG. 10B, the laser ablation is performed in an oxygen atmosphere of 1×10^{-2} Torr for 10 minutes.

Please replace the paragraph beginning at page 26, line 31 with the following rewritten paragraph:

Referring to FIG. 15A, a SrO film 52 is formed on a silicon substrate 51 by a pulse laser deposition technique using a SrCO_3 target. More specifically, the substrate temperature, the target temperature, and the plume temperature are set at 800°C , and laser ablation in accordance with the pulse laser deposition technique is performed under a pressure of 1×10^{-6} Torr for 1 minute and then in an oxygen atmosphere of 5×10^{-4} Torr for 1 minute, thereby producing the SrO film 52.